



B / IFW

1762

Attorney's Docket No. 5308-157IP2

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Das et al.

Serial No.: 10/045,542

Filed: October 26, 2001

For: METHOD OF FABRICATING AN OXIDE LAYER ON A SILICON CARBIDE
LAYER UTILIZING AN ANNEAL IN A HYDROGEN ENVIRONMENT

Confirmation No.: 3570

Group Art Unit: 1762

Examiner: Bret P. Chen

Date: November 2, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INTERVIEW SUMMARY

Sir:

On November 1, 2005, Applicants' representative, David C. Hall, and the Examiner discussed the status of the above-referenced application by telephone. The Examiner and the Applicants' representative discussed the terms "the oxide layer", "existing oxide layer", and "environment containing hydrogen" in Claim 1. The Applicants' representative agreed to amend the term "the oxide layer" to recite "the nitrided oxide layer." The Examiner stated that the finality of the May 18, 2005 Office Action would be withdrawn and a new Office Action would be forthcoming.

Respectfully submitted,

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on November 2, 2005.

Traci A. Brown